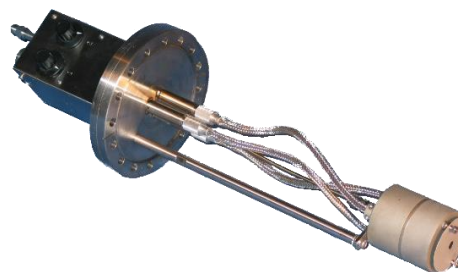
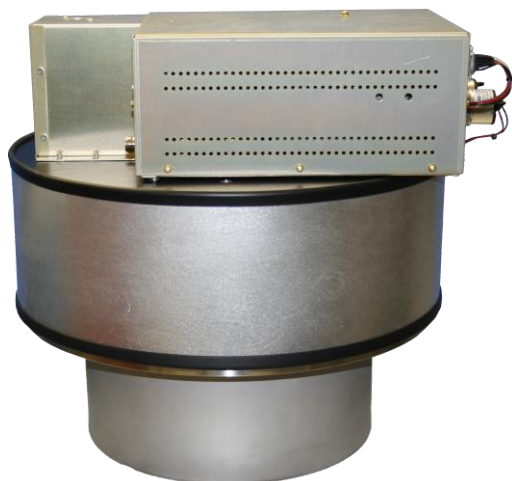


# plasma process group

## High Current Source Solutions



### Features

- **Up To 1000mA Beam Current at 1500V**
- **High Deposition Rates**
- **Rapid Substrate Pre-Clean**
- **Higher Per-Process Throughput**
- **Complete Package – Everything Needed to Upgrade A Deposition Chamber**

### Includes

- **High-Current 16cm RF Ion Source**
  - **Flange or Extension Mount**
- **All-In-One I-Beam Power Supply for up to 800mA Beam Current**
  - **1000mA includes separate 1kW RF Generator**
- **RF Neutralizer & Flange**
- **RF Matching Network & Controller**
- **Complete Cable Package**

### Description

Plasma Process Group is proud to present our new High-Current 16cm RF Ion Beam Source Package! Offered in two configurations, the first features an *Extreme Efficiency* setup, reaching 800mA with a single I-Beam 703 Power Supply equipped with a 500 W RF generator. For 1000 mA, we pair a 1kW RF Generator with an I-Beam 701 Power.

With more current, faster process times may be achievable. Our 800mA option offers a 33% increase in target etch rates, while the 1000mA option provides a whopping 66% increase. At these

*Whether you're in research or production, Plasma Process Group is committed to providing the best support possible. Help is just a phone call away (or email if you prefer). Our people have many years of experience with ion beam sources, systems, and applications, and we're happy to share that with you. Give us a call.*

beam currents, your deposition or etch rates will scale providing rapid process times. These sources are tailored for improving throughput on batch coating systems.

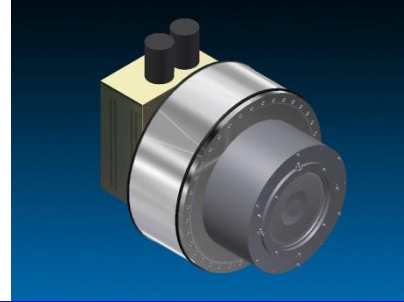
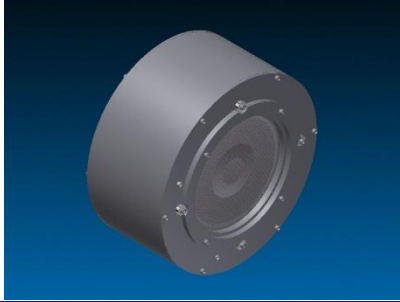
Each High Current Source package is quoted with all the equipment you need to upgrade your existing Ion Beam Deposition or evaporation chamber. A wide variety of grid designs are available to accommodate almost any system configuration. Please give us a call to discuss your specific process needs!

**Specifications**

**16 cm Source**

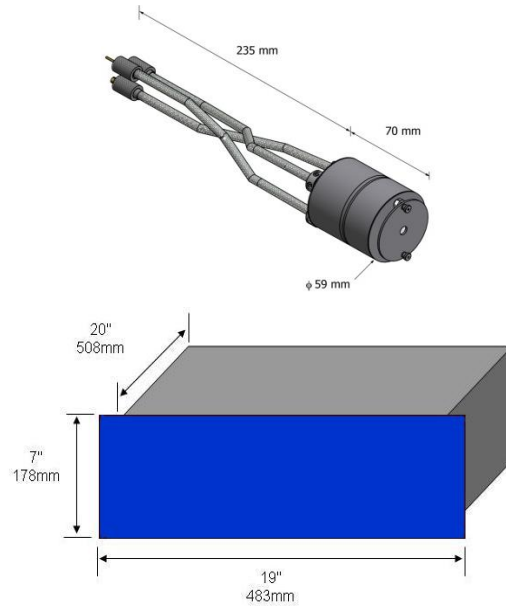
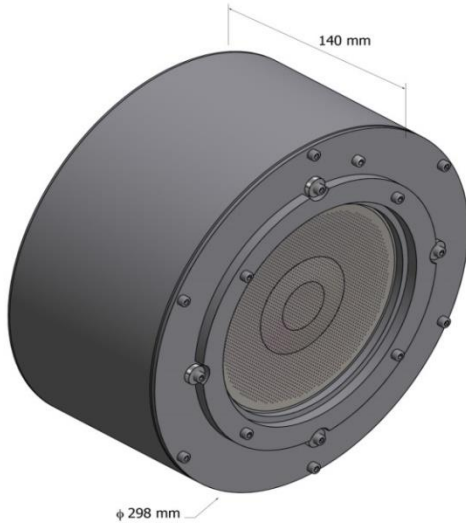
Internal Mount

Flange Mount (16.5" CF)



Ion source	16 cm RF
Beam size at grids	16 cm
Beam current	100-1000 mA
Beam energy	100-1500 eV
Grid material	Molybdenum or Titanium
Beam neutralization	RF Neutralizer
Cooling	Water-Cooled Antenna and Shroud
Power supply	I-BEAM™ 703
Total Package Weight (1 Crate + 1 Box)	114 - 127 Kg (250 - 280 lbs.)

**Dimensions**



**Ordering Information:** High Current ion beam sources are available in two mounting configurations: Flange or Extension. Two output current options are available: 800mA with a single power supply and 1000mA with an additional RF Generator. A variety of grid designs are available for your output ion beam. Please contact us to configure your high current ion beam source.

**High Current Source Package Includes:**

- I-BEAM 703
- 505752A
- 505315A
- 504424B / 504855A
- 504552A / 504553A
- I-BEAM™ 703 RFS/RFN Power Supply w/ built-in 500W RF Generator
- RF and DC Cables for I-Beam High-Current Solution Package, 18' Length
- Communications Cable, I-Beam to RF Matching Network, 6' Length
- RF Neutralizer / 6" Conflat RFN Flange with Matching Network (other sizes available)
- Matching Network for source / Auto Controller for Matching Network



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